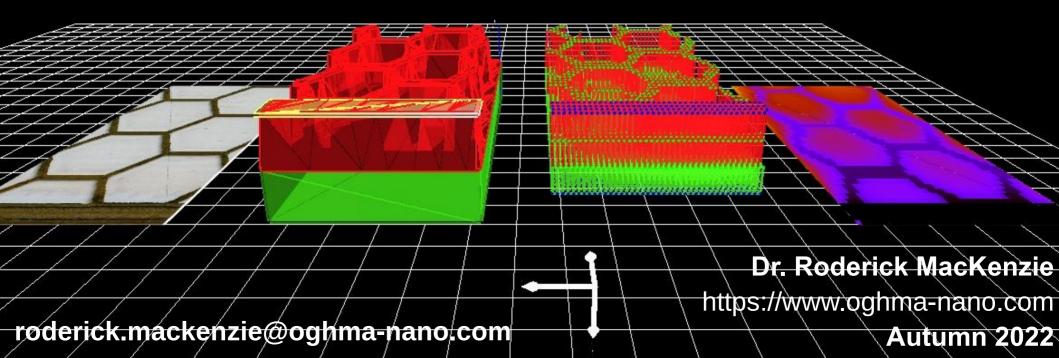
# Editing and scanning electrical parameters in OghmaNano





- •Download all the software used in this talk from:
  - http://www.oghma-nano.com/download.php
- •Please report bugs to:
  - roderick.mackenzie@durham.ac.uk

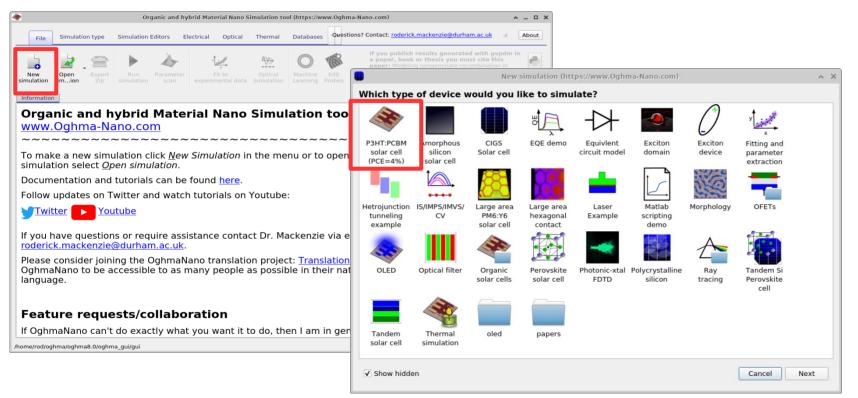


- •Defining device layers
- •Editing the electrical parameters of a material
- •Systematically varying electrical parameters over a range and plotting the results.

# Your first OghmaNano simulation



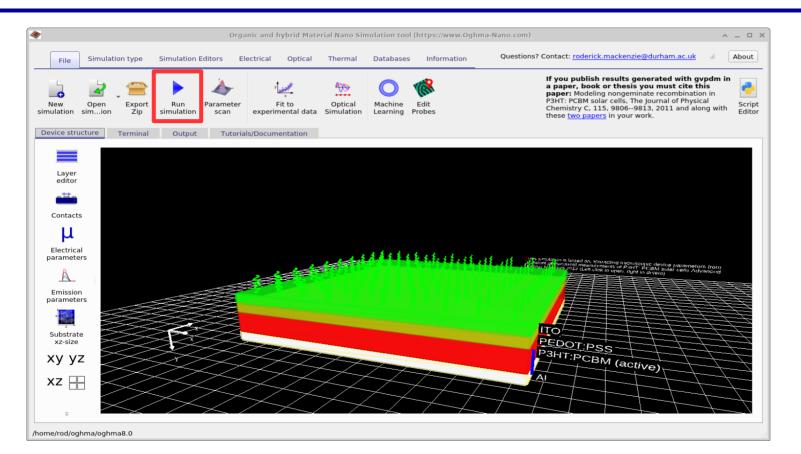
#### •Click on New simulation, in the file menu.



# •Save it somewhere but *not* in the install directory.

## You should get this window.

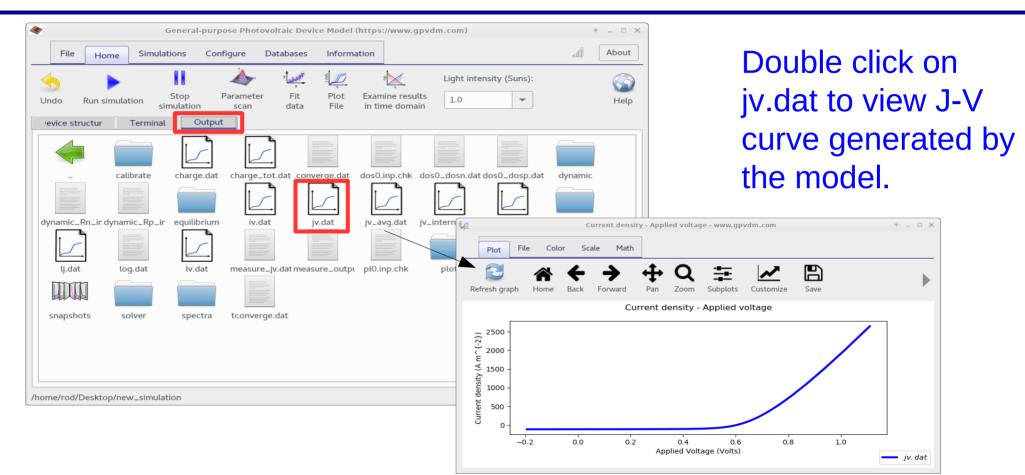




# **Click the play button**

# Examining the results







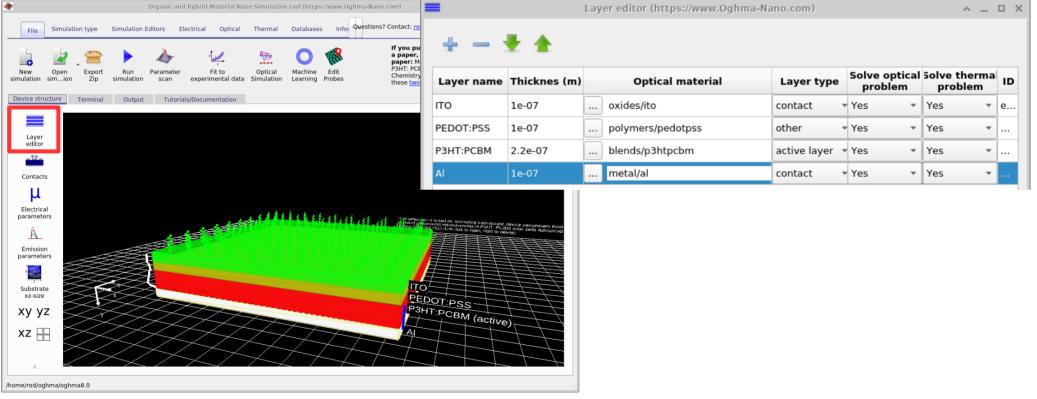
### Defining device layers

•Editing the electrical parameters of a material

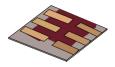
•Systematically varying electrical parameters over a range and plotting the results.

# The layer editor to change the structure of the cell





# The layer editor



Layer editor (https://www.Oghma-Nano.com)						
÷	F 🛧					
Layer name	Thicknes (m)	Optical material	Layer type	Solve optical problem	Solve therma	ID
ІТО	1e-07	oxides/ito	contact •	Yes •	Yes •	e
PEDOT:PSS	1e-07	polymers/pedotpss	other -	Yes 👻	Yes 🔹	
P3HT:PCBM	2.2e-07	blends/p3htpcbm	active layer 🔹	Yes 👻	Yes 👻	
Al	1e-07	metal/al	contact 🔹	Yes 🔹	Yes 🔹	

•Layer name: An English name for the layer, this has no technical significance (Tip: It might not like names with non English characters, i.e. Chinese characters)

•Thickness of the layer: The thickness of the layer in meters.

•Optical material: This points to the n/k data in the materials database. Use the "..." button to select a new material.

•Layer type: Can be contact, other or active.



Layer type	Description	Electrical Equations solved	Optical Equations solved.
active	The electrical model is solved over these layers, each layer gets it's own set of electrical parameters.	Yes	Yes
other	No electrical equations are solved in these layers.	No	Yes
contact	These layers are used to define the electrical contacts, no electrical equations are solved in the layers.	No	Yes



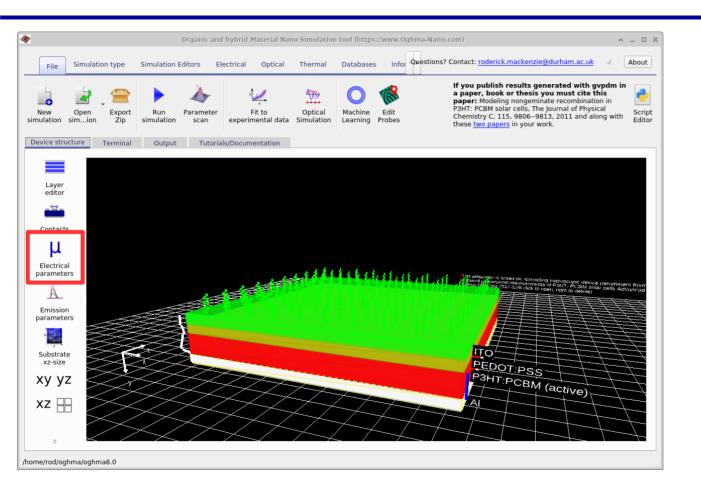
•Defining device layers

#### •Editing the electrical parameters of a material

•Systematically varying electrical parameters over a range and plotting the results.

# Editing the electrical parameters of a material





•Click on the Electrical parameter editor, under the device structure tab.

# This is the electrical parameter window

Sectorical param	neter editor (https://www.Oghma-Nano.com)		^ _ □
Vp     Image: State of the stat	titons Excited states	Confi	gure Help
Free carriers			*
	2.48e-07	Symmetric 👻 m²V	<sup>-1</sup> s <sup>-1</sup>
Hole mobility	2.48e-07	Symmetric 👻 m²V	<sup>-1</sup> s <sup>-1</sup>
Effective density of free electron states (@300K)	1.28e27	m <sup>-3</sup>	
Effective density of free hole states (@300K)	2.86e25	m <sup>-3</sup>	
n <sub>free</sub> to p <sub>free</sub> Recombination rate constant	0.0	m³s	-1
Free carrier statistics	Maxwell Boltzmann - analytic	▼ type	2
Non-equilibrium SRH traps			
DoS distribution	Exponential		Edit
Electron trap density	3.8e26	m <sup>-3</sup>	eV <sup>-1</sup>
Hole trap density	1.45e25	m <sup>-3</sup>	eV <sup>-1</sup>
Electron tail slope	0.04	eV	
Hole tail slope	0.06	eV	*

•Here you can edit the electrical parameters of the electrically active layers. Each *electrically active* layer will get a new tab here.

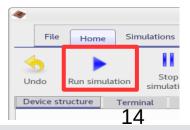


# Editing an electrical parameter...the trap density....

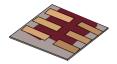
	Electrical para	neter editor (https://www.Oghn	na-Nano.com)	^	_
	namic H traps SRH traps Ex	citons Excited states		¢ Configure	He
Free carriers					
Electron mobility		2.48e-07	Symmetric 💌	m²V <sup>-1</sup> s <sup>-1</sup>	
Hole mobility		2.48e-07	Symmetric 👻	m²V <sup>-1</sup> s <sup>-1</sup>	
Effective density of fre	ee electron states (@300K)	1.28e27		m <sup>-3</sup>	
Effective density of fre	ee hole states (@300K)	2.86e25		m <sup>-3</sup>	
n <sub>free</sub> to p <sub>free</sub> Recombina	ition rate constant	0.0		m <sup>3</sup> s <sup>-1</sup>	
Free carrier statistics		Maxwell Boltzmann - analytic	¥	type	
Non-equilibrium SR	H traps				
DoS distribution		Exponential		Edit	
Electron trap density		3.8e26		m <sup>-3</sup> eV <sup>-1</sup>	
Hole trap density		1.45e25		m⁻³ eV⁻¹	
Electron tail slope		0.04		eV	
Hole tail slope		0.06		eV	

a) Make the density of trap state symmetric at  $1 \times 10^{24}$  m<sup>-3,</sup> and rerun the simulation.

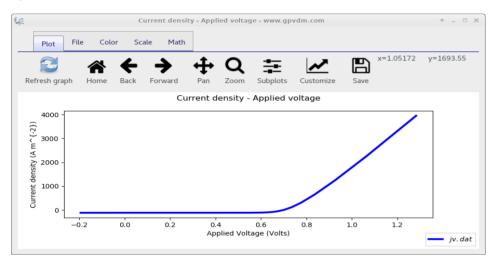
b) Now re-plot the JV curve (**jv.dat**), also find the (**sim\_info.dat**) file, double click on it and find the power conversion efficiency.



# You should have results which look a bit like this:



### jv.dat:



### sim\_info.dat:

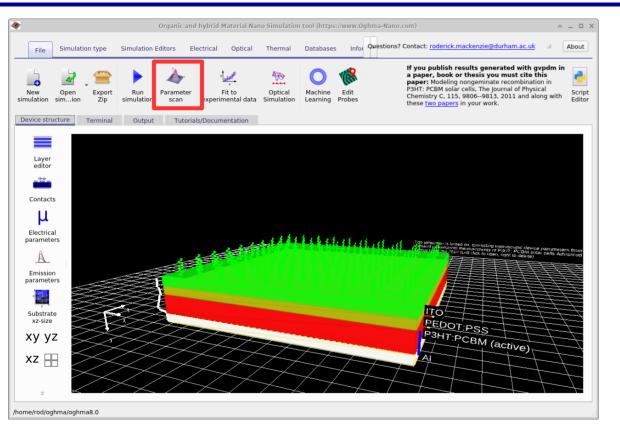
			6
	Simulation Info	rmation	
Fill factor	0.801681	a.u.	
Power conversion efficiency	6.317818	Percent	
Max power	63.178183	Watts	
V <sub>oc</sub>	0.697817	V	
Recombination time constant at V	oc 6.033818e-04	s	
Recombination rate at Voc	2.053384e+26	m <sup>-3</sup> s <sup>-1</sup>	
Average carrier density at P <sub>max</sub>	2.597280e+22	m <sup>-3</sup>	
Recombination time constant	1.782948e-03	m-1	
Trapped electrons at Voc	1.868796e+20	m <sup>-3</sup>	
Trapped holes at Voc	6.739736e+21	m <sup>-3</sup>	
Free electrons at Voc	9.096213e+22	m <sup>-3</sup>	
Free holes at Voc	9.051892e+22	m <sup>-3</sup>	
J <sub>sc</sub>	-1.129337e+02	A m <sup>-2</sup>	
Total carriers (n+p)/2 at Voc	1.817027e+23	m <sup>-3</sup>	



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# Varying a parameter many times using the Parameter Scan, window.



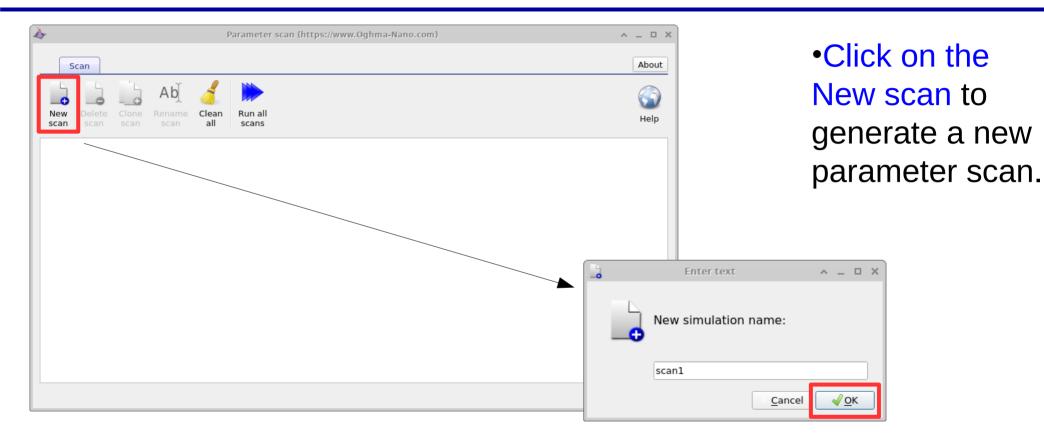
•Often we want to change a simulation parameter several times to understand how a parameter affects a device.

# •To do this, use the *Parameter Scan tool*

# •Click on the parameter scan tool

### The parameter scan window





# The parameter scan window



4	Parameter scan (https://www.Oghma-Nano.com)	~ _ □ ×		
Scan		About		
New Delete Clone Rename C	dean Run all all scans	Help		
		<b>A</b>	oghma	~ _ ¤ X
scan1		Simulations	2	About
		Commands Output		
		Parameter to change	Values	Opperation
		theme includes the second s		
		/home/rod/oghma/oghma8.0/scan1(scan0.inp)		

# A new line should appear...



simulations	About	•Add a r button.	new line by clic	king the
Run scan     Plot simulation     Notes       Commands     Output       Image: State of the state of	Simulations Simulations Run Plot Clean Notes Commands Output Commands Output	oghma		About
	Parameter to change Select parameter 0.0 0.0	Values	Opperation scan	•
/home/rod/oghma/oghma8.0/scan1(scan0.inp)				

# A new line should appear...



>		oghma			^ _ □ ×
Simulations					About
Run scan Plot Simulation	Notes				
Commands Output					
+ - 🛃 🛧 🖻					
		Values	Opp	eration	
Select parameter	0.) 0.0		scan	-	

•Click on the '...' icon, expand the tree as shown, select 'Hole trap density' and click OK.

•Then select *epitaxy/P3HT:PCBM/Drift diffusion/Electron trap density* 

Select simulation parameter (https://www.Oghma-Nano.com) 🔹 🗕 🗖	×
data.epitaxy.P3HT:PCBM.Drift diffusion.Electron trap density	
Effective density of free hole states	•
Image: mage: ma	
Sector Statistics	
× ss_srh_enabled	
(×) n_{1}	
(x) p_{1}	
<pre>(x) tau_{n}</pre>	
<pre>(x) tau_{p}</pre>	
DoS distribution	
• • complex_lumo	
<u> </u>	
Electron trap density	
× Hole trap density	
× Electron tail slope	
× Hole tail slope	
Perovskite ion density	
() ion mobility	
OK	

# The parameter scan window...



\$	oghma		~ _ <b>□</b> ×
Simulations			About
Run scan Plot Simulation Run			
Commands Output			
Parameter to change epitaxy/P3HT:PCBM/Drift diffusion/Electron mobility y 0.0	Values	<b>Opperation</b>	
		•	
This shows the parameter	er 📃		X
which will be edited.	1e25 1e here. Th densitie	ese (1e24 e26) values in ney are the trap s we are going over (units are )	This selects the operation which will be performed. (more explained later)

# But we want to simulate a symmetric device (where Ntraph=Ntrape)...



À	oghma		^ _ O X
Simulations			About
Run Plot Simulation Notes			
Commands Output			
÷ - 🝷 🛧 🔤			
Parameter to change		Values	Opperatior
epitaxy/P3HT:PCBM/Drift diffusion/Electron trap density		1e24 1e25 1e26	scan
epitaxy/P3HT:PCBM/Drift diffusion/Hole trap density		0.0 0.0	scan
		·	

So using the '+' button add another row and then using the '...' buttons make it look like the above..

# But we want to simulate a symmetric device (where Ntraph=Ntrape)...



4	oghma		^ _ O X
Simulations			About
Run scan Plot Simulation Notes			
Commands Output			
÷ — 🛃 🛧 🖾			
Parameter to change	Values	Opperation	
epitaxy/P3HT:PCBM/Drift diffusion/Electron trap density	1e24 1e25 1e26	scan 🔹	
epitaxy/P3HT:PCBM/Drift diffusion/Hole trap density	duplicate	epitaxy/P3HT:PCBM/Drift diffusion/Electron trap density 👻	

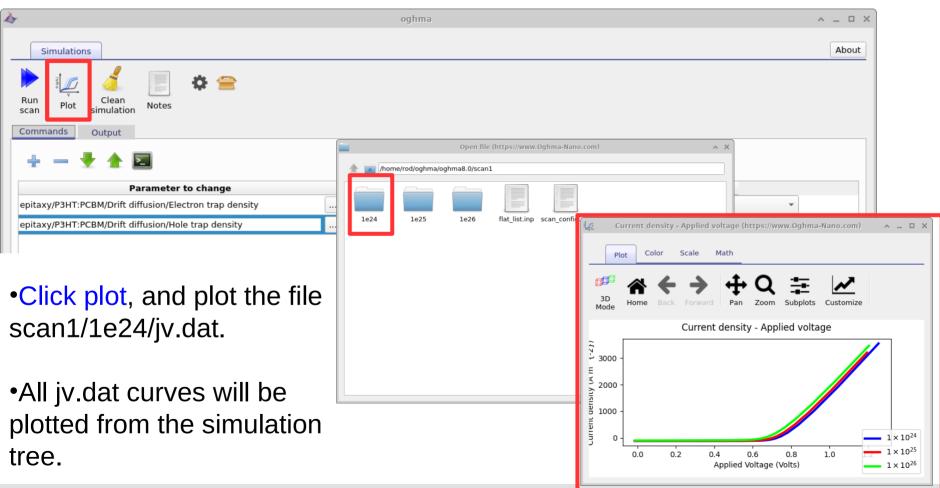
•Then from this menu select, 'epitaxy/P3HT:PCBM/dos/Electron trap density'.

•This means that the values for Hole trap density will follow that of the Electron trap density.

•Now click 'Run scan'...., it will run the simulations in parallel across all cores of your CPU.

# Plotting the results.







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